

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims, including those in the First Preliminary Amendment, in the application:

Listing of Claims:

Claim 1 (currently amended): A hollow cathode sputtering target ~~comprising~~ having an inner ~~bottom~~ face ~~having~~ with a surface roughness of $R_a \leq 1.0 \mu\text{m}$.

Claims 2-6 (canceled).

Claim 7 (currently amended): A surface finishing method of a hollow cathode sputtering target ~~characterized in~~ comprising the steps of polishing and etching ~~the bottom an~~ inner face of the target so as to make the surface roughness of the inner ~~bottom~~ face $R_a \leq 1.0 \mu\text{m}$.

Claim 8 (canceled).

Claim 9 (new): A hollow cathode sputtering target according to claim 1, wherein said surface roughness of said inner face is $R_a \leq 0.5 \mu\text{m}$.

Claim 10 (new): A hollow cathode sputtering target according to claim 9, wherein said inner face of said hollow cathode sputtering target includes a cylindrical peripheral face and a bottom face, wherein a surface roughness (R_a) of said bottom face is equal to or less than a surface roughness (R_a) of said cylindrical peripheral face.

Claim 11 (new): A hollow cathode sputtering target according to claim 10, wherein said target has an outer peripheral edge with a rough face.

Claim 12 (new): A hollow cathode sputtering target according to claim 11, wherein said rough face of said outer peripheral edge is an abrasive blasted face.

Claim 13 (new): A hollow cathode sputtering target according to claim 12, wherein said hollow cathode sputtering target is formed from a cladding material.

Claim 14 (new): A hollow cathode sputtering target according to claim 13, wherein said bottom face is a non-erosion portion of said inner face of said target.

Claim 15 (new): A hollow cathode sputtering target according to claim 1, wherein said inner face of said hollow cathode sputtering target includes a cylindrical peripheral face and a bottom face, wherein a surface roughness (Ra) of said bottom face is equal to or less than a surface roughness (Ra) of said cylindrical peripheral face.

Claim 16 (new): A hollow cathode sputtering target according to claim 15, wherein said target has an outer peripheral edge with a rough face.

Claim 17 (new): A hollow cathode sputtering target according to claim 16, wherein said rough face of said outer peripheral edge is an abrasive blasted face.

Claim 18 (new): A hollow cathode sputtering target according to claim 17, wherein said hollow cathode sputtering target is formed from a cladding material.

Claim 19 (new): A hollow cathode sputtering target according to claim 18, wherein said bottom face is a non-erosion portion of said inner face of said target.

Claim 20 (new): A hollow cathode sputtering target according to claim 1, wherein said target has an outer peripheral edge with a rough face.

Claim 21 (new): A hollow cathode sputtering target according to claim 20, wherein said rough face of said outer peripheral edge is an abrasive blasted face.

Claim 22 (new): A hollow cathode sputtering target according to claim 1, wherein said hollow cathode sputtering target is formed from a cladding material.

Claim 23 (new): A hollow cathode sputtering target according to claim 1, wherein said inner face of said hollow cathode sputtering target includes a cylindrical peripheral face and a bottom face, and wherein said bottom face is a non-erosion portion of said inner face of said target.

Claim 24 (new): A method according to claim 7, wherein said surface roughness of said inner face is made to be $Ra \leq 0.5 \mu m$ during said polishing and etching step.

Claim 25 (new): A method according to claim 24, wherein said inner face of said hollow cathode sputtering target includes a cylindrical peripheral face and a bottom face, and wherein said bottom face is made to be a non-erosion portion of said inner face of said target.

Claim 26 (new): A method according to claim 7, wherein said inner face of said hollow cathode sputtering target includes a cylindrical peripheral face and a bottom face, and wherein said bottom face is made to be a non-erosion portion of said inner face of said target.